

*Status of the Claims*

The listing of claims will replace all prior versions, and listings of claims in the application.

1-17 (Cancelled)

18. (Currently Amended) A relay lens system positioned between a delimiter plane and a pattern generator plane of a lithography system, comprising:

a first lens group consisting of three lenses that decrease numerical aperture of a received beam of radiation;

a second lens group having at least one lens that receives the beam of radiation from the first lens group and controls characteristics of the beam of radiation at a pupil plane;

a third lens group consisting of a single lens element that receives the beam of radiation from the second lens group and controls field characteristics of the beam of radiation at a patterning device plane;

an aperture stop positioned between the first and second lens groups; and

a fold mirror positioned between the second and third lens groups.

19. (previously presented) The system of claim 18, wherein the second lens group consists of two lenses.

20. (previously presented) The system of claim 18, wherein the second lens group consists of three lenses.

21. (previously presented) The system of claim 18, wherein one of the three lenses in the first lens group is a meniscus lens.

22. (previously presented) The system of claim 18, wherein two of the three lenses in the first lens group are biconvex lenses.

23. (previously presented) The system of claim 22, wherein one of the two biconvex lenses has an aspherical surface.

24. (previously presented) The system of claim 18, wherein the at least one lens in the second lens group has at least one aspherical surface.

25. (previously presented) The system of claim 18, wherein the at least one lens in the second lens group has at least one convex surface.

26. (previously presented) The system of claim 18, wherein the single lens in the third lens group comprises two spherical surfaces.

27. (cancelled)

28. (currently amended) The system of claim 18, further comprising:

a light source positioned before the first, ~~second, and third~~ lens group groups; and

a pattern generator positioned after the third lens group in the pattern generator plane.

29. (new) The system of claim 18, wherein the characteristics controlled by the second lens group comprise at least one of pupil aberration correction, pupil shape correction, ellipticity correction, and telecentricity correction.

30. (new) The system of claim 18, wherein the field characteristics controlled by the third lens group comprises at least one of creating a desired field size at the pattern generator plane and correcting telecentricity.